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Introduction

It is with great pleasure that we present these proceedings from the Seventh Conference on Thin Film Physics and Application, held 24–27 September 2010 in Shanghai, China.

This conference (TFPA2010) is intended to report on the latest advances and innovations in thin film from growth, characterization, and physics, to the applications and associated devices; as well as to serve as a discussion forum for exchanging information about the development, application, and experimental results from thin film systems by bringing together researchers, academics, manufacturers and students working in the field. The event aims to cover the most up-to-date and diverse thin films such as nanostructure films, ferroelectric and piezoelectric films, magnetic films, superconductor films, organic and polymer films, micro/nano-fabrications and characterizations, photonics and MEMS devices, solar cells, and others.

The conference was very successful with over 110 contributed papers (as oral or poster presentations) together with 31 invited talks delivered from authors of diverse international affiliations (i.e., United States, Japan, China, France, Germany, Russia, and others). By organizing TFPA2010, it is our sincere hope to help promote and broaden the diffusion of the research activities in the thin film field.

We would like to express our sincere appreciation to the program committee and session chairs, to colleagues who participated in the conference, to the SPIE staff, and to all our hosts and meeting sponsors whose contributions were all essential to the success of this conference.

Junhao Chu
Zhanshan Wang


7th International Conference on Thin Film Physics and Applications